

Inventor: Mark Fischer et al.

EL 844046498 #2

Title: Semiconductor Processing Methods of Forming a Conductive Projection and Methods of Increasing Alignment Tolerances

Assignee: Micron Technology, Inc.



INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.


The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 09/507,193, filed February 18, 2000.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: July 18, 2001

Attorney:


Bernard Berman, Reg. No. 37,279
WELLS, ST. JOHN, ROBERTS,
GREGORY & MATKIN P.S.
601 W. First Ave., Suite 1300
Spokane, WA 99201-3828
(509) 624-4276